

REMARKS

1. Claims 12, 16, 17, 26, 32-40 and 42-43 were rejected under §102(b) over Vaidya et al. This rejection is moot in view of the cancellation of claims 12 and 16-18, and the incorporation of the subject matter of claim 27 into claim 26.

2. Claims 12, 17-18, 26-41 and 44-46 were rejected under §102(b) over Iijima et al. This rejection is respectfully traversed for the following reasons.

The claimed invention is directed to a process for the continuous deposition of a coating of an HTS tape, which includes, among other features, translating a substrate through a deposition chamber and along a substrate block, the substrate block having gas channels extending therethrough. In addition, gas is injected through the gas channels of the substrate block and onto the substrate, and depositing is carried out by depositing a coating material on the substrate translating along the substrate block, the coating being a buffer layer having a biaxial texture. According to the claimed invention, gas is injected so as to flow through the gas channels of the substrate block and onto the substrate. For an illustration of an example of the foregoing structure, please refer to FIG. 3 illustrating substrate block 144 having gas channels 316 which terminate at the surface along which the substrate 228 translates, so as to direct gas flow onto the back side of the substrate.

While the PTO has apparently relied upon Iijima et al. for teaching of all features of the claimed invention, it is quite clear that Iijima et al. fail to disclose such a process, incorporating such a substrate block and executing gas flow as claimed. In reference to FIG. 5, Iijima et al. disclose a substrate block 23, the back side of which is contacted against pedestal 60, pedestal 60 receiving gas flow due to arrangement of inflow and outflow pipes 62, 63. Iijima et al. specifically teach that the back surface 60b of pedestal 60 is hermetically sealed, and that the gas does not flow into the substrate block, and certainly not through the substrate block and onto the substrate, as claimed. See paragraph 65 of Iijima et al.

Since it is quite clear that Iijima et al. fail to disclose or even remotely suggest all features of the claimed invention, reconsideration and withdrawal of the §102(b) rejection are respectfully requested.

Applicants respectfully submit that the present application is now in condition for allowance. Accordingly, the Examiner is requested to issue a Notice of Allowance for all pending claims.

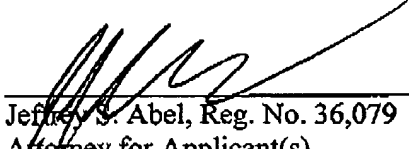
Should the Examiner deem that any further action by the Applicants would be desirable for placing this application in even better condition for issue, the Examiner is requested to contact Applicants' undersigned attorney at the number listed below.

Applicants do not believe that any additional fees are due, but if the Commissioner believes additional fees are due, the Commissioner is hereby authorized to charge any fees which may be required, or credit any overpayment, to Deposit Account Number 50-2469.

Respectfully submitted,

Date

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